

# Strontium Titanate $\text{SrTiO}_3$

## Sputtering Targets



Advanced Engineering Materials



### Applications

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- Ferroelectric
- CMOS
- Thin film capacitor

### Features

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- High purity
- Custom Sizes Available

### Process

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- Manufacturing
  - Cold pressed
  - Sintered
  - Elastomer bonded to backing plate
- Cleaning and final packaging
  - Cleaned for use in vacuum
  - Protection from environmental contaminants
  - Protection during shipment

### Options

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- 99.9% Minimum Purity
- Up to 12.0" Diameter Targets Available
- Planar Tiles Up to 8" X 5" for Larger Target Configurations

## Specifications

### Typical Analysis - 99.9% (3N) Purity

Metallic Impurities, ppm by weight

Al	Ba	Bi	Ca	Cl	Co	Cr	Fe	Hf	K
<5	<5	<5	<15	<15	<5	<5	<5	<20	<5

Mg	Mn	N	Na	Ni	Pb	S	Sb	Si	Sn
<5	<5	<50	<50	<5	<5	<5	<5	<5	<5

Theoretical Density	5.1 g/cc
Typical Density	3.66 g/cc
Sputter	RF
Max Power Density (Watts/Square Inch)	20
Appearance	White/Beige
Z Ratio	0.31
Particle Size	D50

## Advanced Engineering Materials

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